

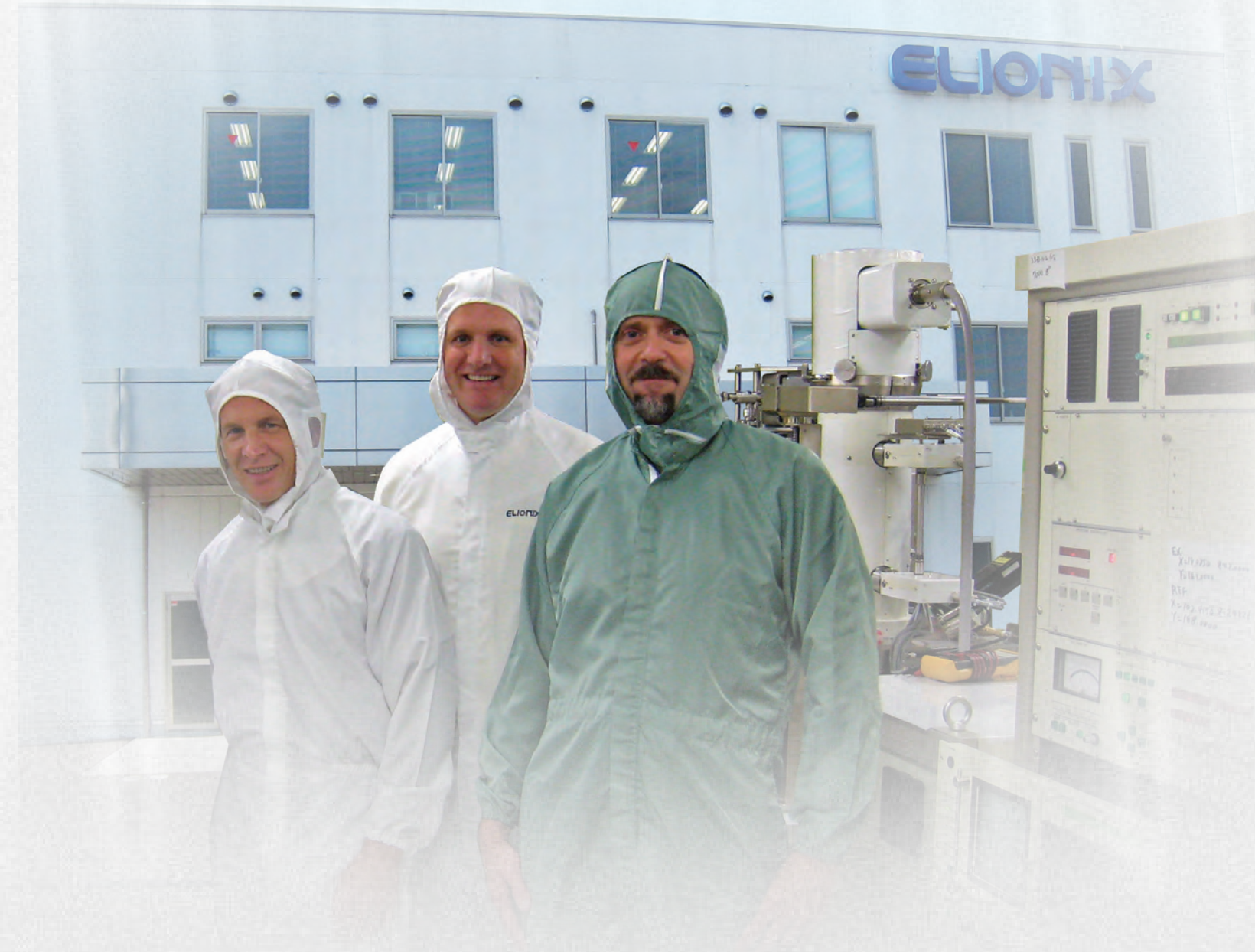
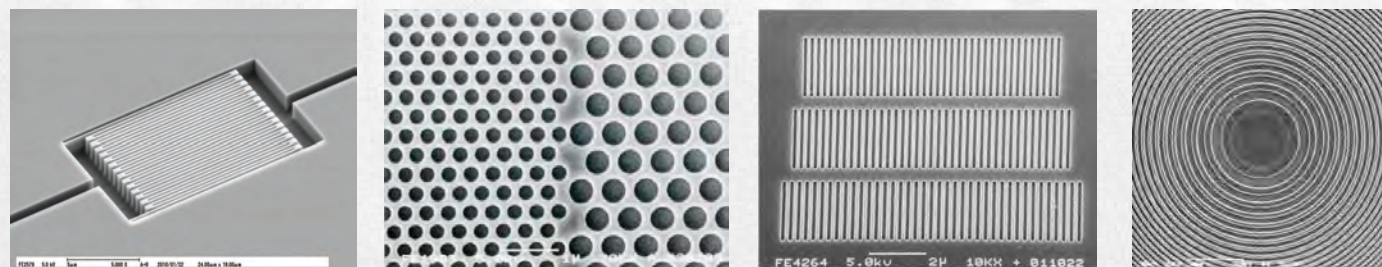
# Nanotechnology for the Next Generation



## Ultra High Precision Electron Beam Lithography Systems



	ELS-F125	ELS-F100	ELS-7500EX
<b>Electron Optics:</b>			
Electron Beam Shape	Spot (Gaussian)	Spot (Gaussian)	Spot (Gaussian)
Emitter	ZrO/W TFE	ZrO/W TFE	ZrO/W TFE
Acceleration Voltage (max.)	125kV	100kV	50kV
Beam Diameter (min.)	1.7nm	1.8nm	2.0nm
Beam Current	5pA to 100nA	20pA to 100nA	1pA to 50nA
<b>Lithography:</b>			
Line Width (min.)	5nm	6nm	10nm
Stitching Accuracy	10nm	15nm	30nm
Overlay Accuracy	15nm	15nm	30nm
Field Size (max.)	500 $\mu$ m sq. (at 125kV)	1000 $\mu$ m sq. (at 100kV)	1200 $\mu$ m sq. (at 50kV)
Specimen Size (max.)	8" wafer/mask	8" wafer/mask	6" wafer/mask



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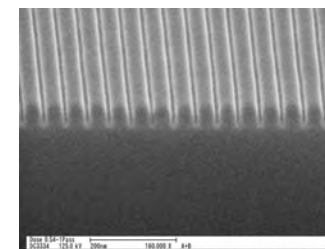
***Celebrating Over 35 Years of Creativity and Innovation***



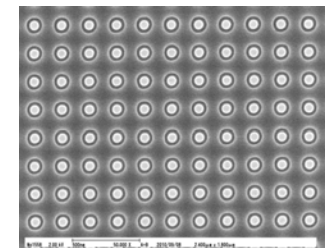
# Ultra High Precision Electron Beam Lithography



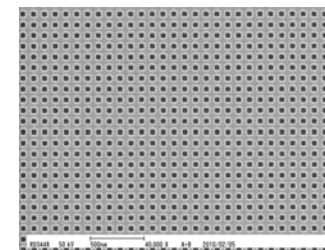
- Fine Patterned Lines
- Small Beam Diameter at High Beam Currents
- Uniform Large Field Writing
- Advanced Overlay & Stitching



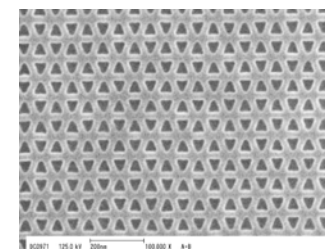
5nm Lines



15nm Rings



50nm Squares



50nm Triangles



ELS-F125



ELS-F100



ELS-7500EX